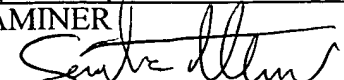


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				APPLICANT Lizhong Sun, et al.			
				FILING DATE August 24, 2000		GROUP 2812 1746	
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)

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49959-118

SERIAL NO.
09/645,690

APPLICANT
Lizhong Sun, et al.

FILING DATE
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